

Indo-French Workshop on Multifunctional Molecular and Hybrid Devices

# Field Effect Transistors based on Poly(3-hexylthiophene) with 3-aminopropyltrimethoxy silane multilayer modified gate dielectric



#### **Outline**

- Introduction
- Role of self-assembly monolayers (SAM) in OFETs
- **❖ APTMS Multilayers /monolayer:**

#### Growth and characterization

- Influence of surface modification on P3HT
- FET: Fabrication and characterization
- Conclusions

### **OFET: Key Features**

- Tailoring properties as per demand
- Easy processing spin coating, inkjet printing, screen printing etc.
- Low-temperature deposition
- Flexibility
- Applications in switching devices, flexible sensors, printed electronics such as RF-ID tags, integrated circuits

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#### **Materials**

#### **Small molecules**

#### **Large Molecules**

Polyacetylene

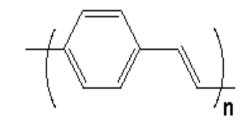
Phthalocyanine

Polythioph ene

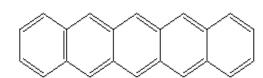
$$+$$
 $\left\langle \bigcirc \right\rangle_{n}$ 

Polyphenylene

Sexithiophene



Polyphenylenevinylene



Pentacene

#### **Parameters**

- Mobility
- ❖ ON/OFF Ratio
- Threshold voltage
- Subthreshold slope
- Transconductance
- Current leakage

#### Important Issues

**Material Science** 

**Charge transport** 

**Novel Materials Structure** 

#### **Device Physics**

Dielectric

Fabrication Details

Device Geometry

### Why is structure important?

#### Structure influences electronic properties

#### Information Requirements

Molecular orientation (few Å)

Interfacial structure (few Å)

Crystal/ Amorphous domains (few nm)

Macroscopic Defects (few nm)

**Grain boundaries, traps** 

### Interfacial Engineering: SAM

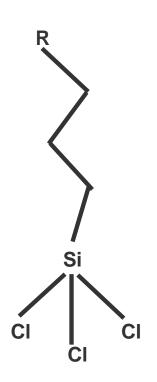
#### Interface between dielectric and semiconductor

Change in morphology, molecular ordering and packing, crystallinity of semiconductor

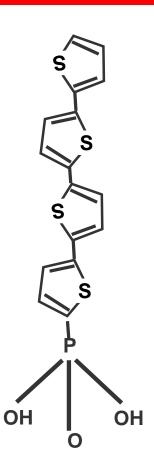
Interface between metallic contacts and semiconductor

Better charge injection at the interface

#### **Some SAM Structures**







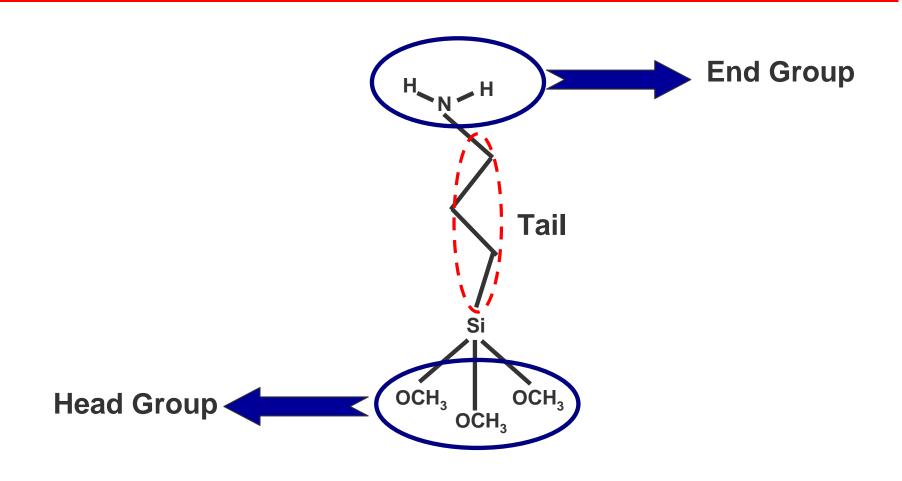
**Organic trichlorosilanes** 

**Organothiols** 

(quarterthiophene) phosphonic acid

R: CH<sub>3</sub>, C<sub>2</sub>H<sub>5</sub>, etc

#### **APTMS**: *Molecular Structure*

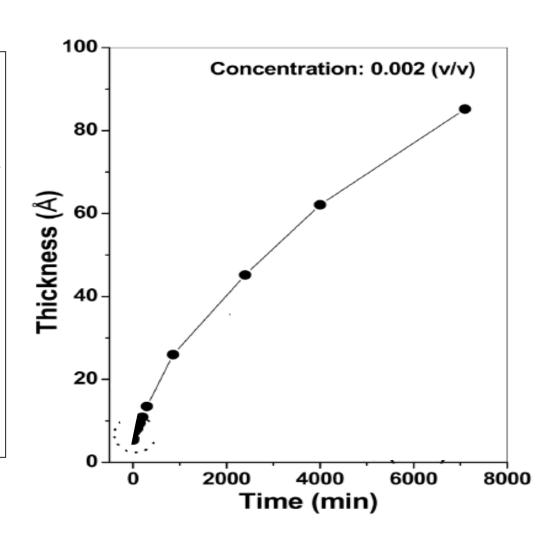


#### APTMS Growth: Monolayer/ Multilayers

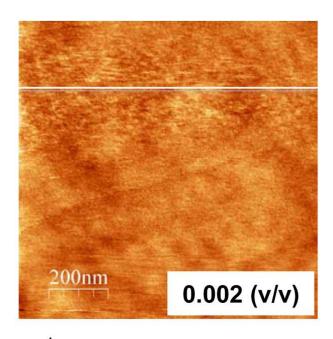
#### **Solution Growth:**

APTMS in dry toluene under inert atmosphere for 30 mins.

Thickness depends on concentration and time

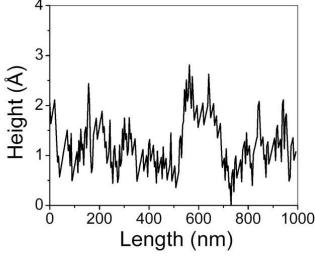


#### APTMS Monolayer: Characterization



Roughness < 1 Å

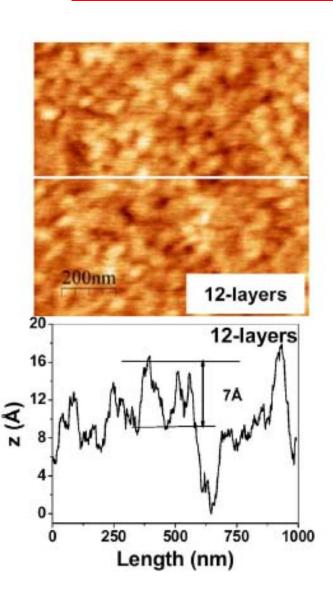
DI water contact angle < 15°



Molecule Thickness ~ 6.5 Å,

indicates formation of well organized monolayer

#### **APTMS Multilayers:** Characterization



Roughness

7Å

DI water contact angle

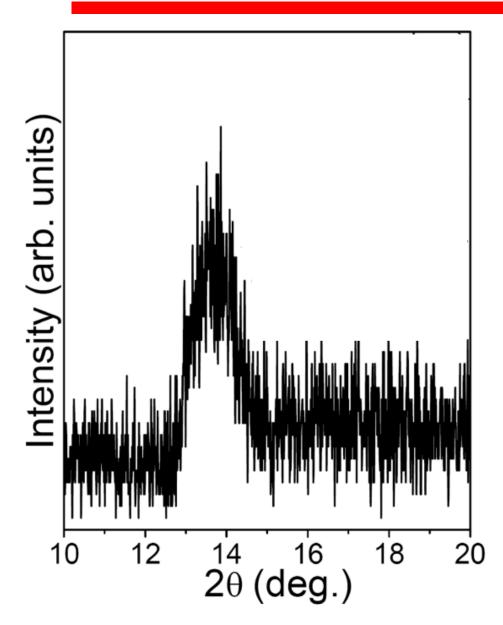
<42°

**Thickness** 

~ 78.5 Å

corresponds to 12 monolayers

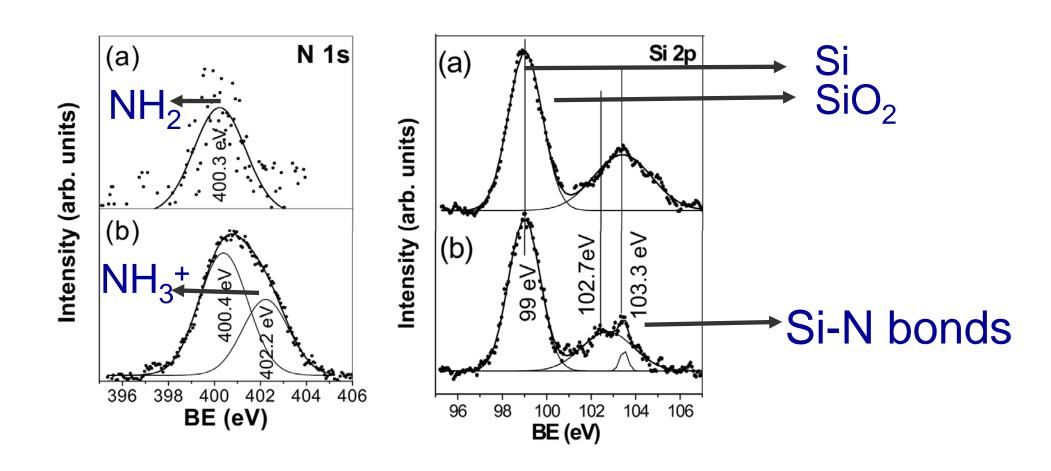
#### **APTMS Multilayers: XRD Characterization**



Length of APTMS molecule~6.4 Å

Layer by layer self- assembly of APTMS multilayer

#### **APTMS:** XPS Characterization



(a) Monolayer

(b) 12-layered APTMS

#### **Growth Mechanism**

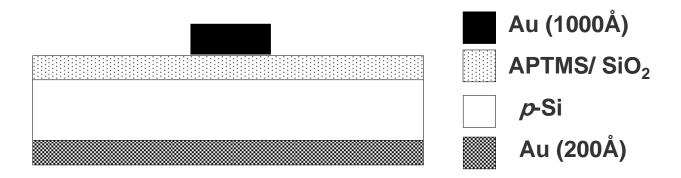
APTMS molecule gets chemisorbed on SiO<sub>2</sub>.....

......  $NH_2$  group of APTMS gets protonated by  $H_2O$  or by slight acidity of solvent to form  $NH_3^+$  ions....

......Hydrolyzed APTMS molecule can also react with NH<sub>2</sub> group of monolayer via Si-N bonding.....

....Bilayer formation takes place through Si-N bonds & NH<sub>3</sub> + ions

#### APTMS Multilayers: C-V on MIS Structure



Structure	C <sub>i</sub> (nF/cm²)	3
SiO <sub>2</sub>	15	3.8
APTMS	70	4.19

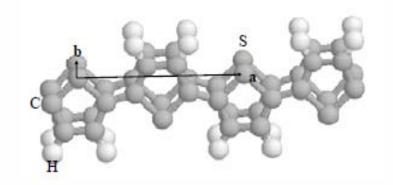
#### P3HT Film

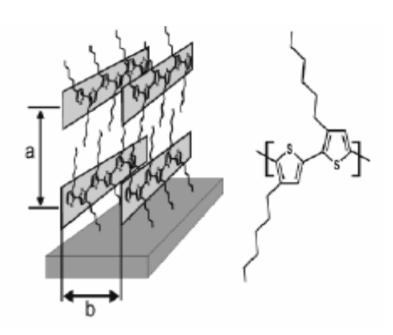
#### P3HT

$$a = 33.6 \text{ Å}, b = 7.66 \text{ Å}$$

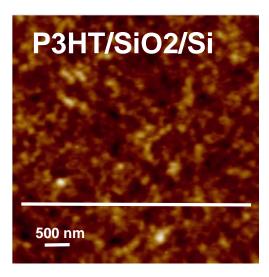


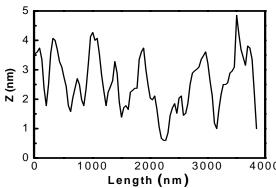
But we need devices working in ambient conditions!!

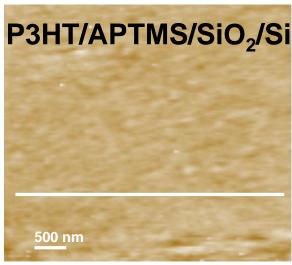


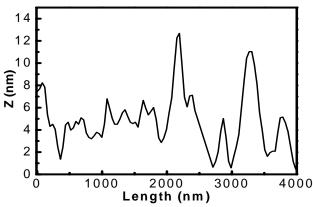


### P3HT on APTMS Multilayers: AFM Study







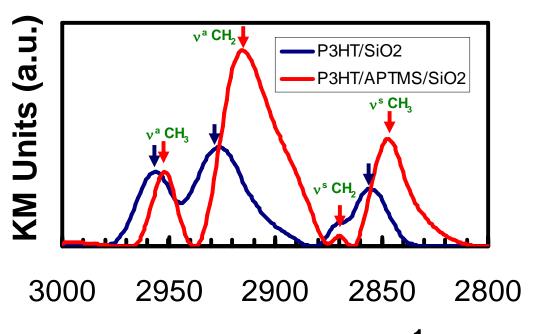


Without APTMS ~ 40 Å Roughness:

With APTMS  $\sim 7 \text{ Å}$ 

#### P3HT on APTMS Multilayers: FTIR Study

#### Aliphatic hexyl stretching region



Reduction in wave numbers of  $v^a$  CH<sub>2</sub> 2916 cm<sup>-1</sup>.

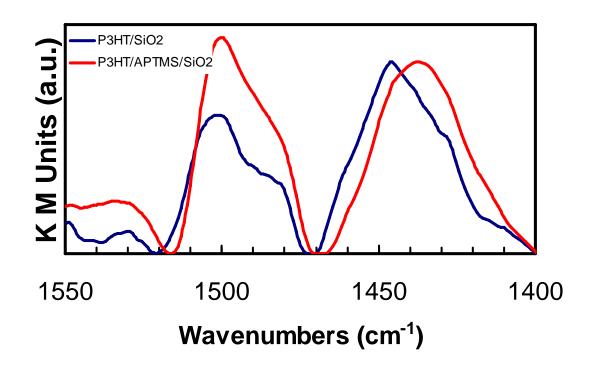
Reduction in peak width and an increase in intensity of 2916 cm<sup>-1</sup> peak.

Wavenumbers (cm<sup>-1</sup>)

<u>Transformation from disordered to crystalline films!</u>

#### P3HT on APTMS Multilayers: FTIR Study

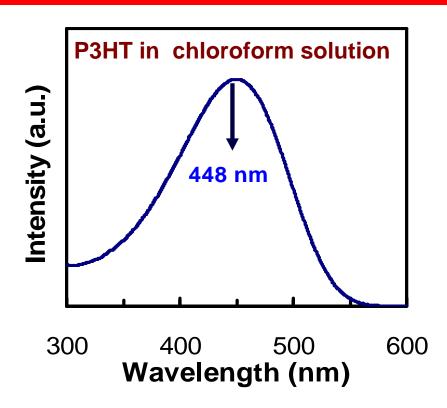
#### Fingerprint region



Intensity peak ratio =  $v^a/v^s$  corresponding to C=C vibrations of thiophene ring

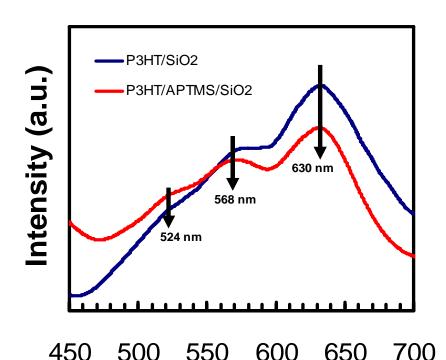
Increase in conjugation length of polymer backbone after APTMS modification!

#### P3HT on APTMS Multilayers: UV-Vis Study



Peak at 448 nm due to  $\pi$ - $\pi$ \* electronic transition

#### P3HT on APTMS Multilayers: UV-Vis Study



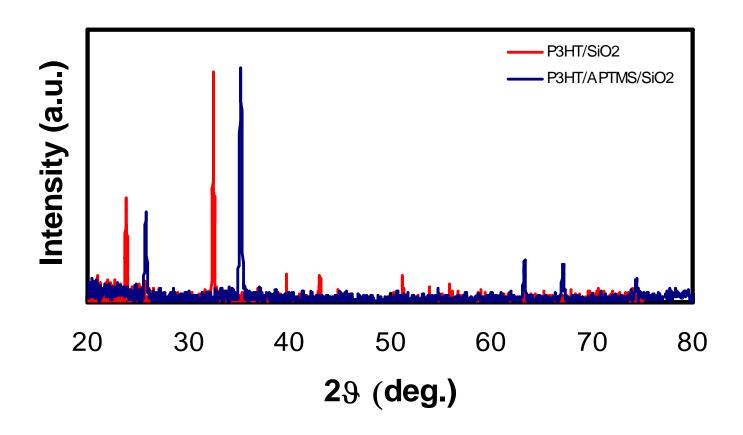
Wavelength (nm)

Red shift in the optical spectra

Additional peaks observed in films

Increase in conjugation length & crystalline order after APTMS modification!

### P3HT on APTMS Multilayers: XRD Study



### Why is the improvement?

Crystallinity, molecular ordering and conjugation length

- SiO<sub>2</sub> surface energy~ 72 mN/m
- ❖ Chemical Modification of SAM with APTMS, (water contact angle ~ 42°), surface energy ~46-50 mN/m
- ❖ This is not sufficient as chemical modification with apolar (-CH₃) group terminated surface result in reduced surface energy (23-25 mN/m).

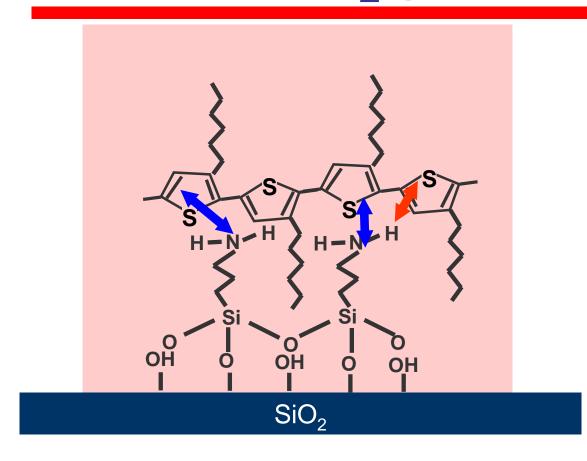
### What is the deciding factor?

Improvement may be the result from a combination of a number of effects, such as changes in surface energy, surface roughness, molecular orientation, and reduced defects

Role of dielectric surface treatment is still not entirely clear

More information is needed to get a clear picture

### Role of –NH<sub>2</sub> group



Presence of –NH<sub>2</sub> group at interface between P3HT and substrate results in

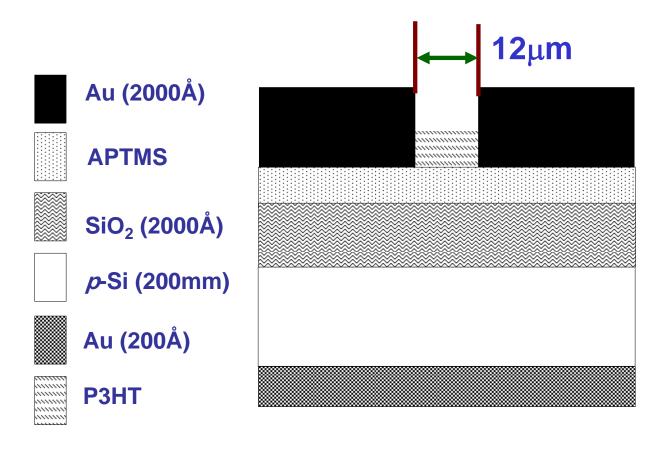
edge-on conformation

Better charge transport

Leads to higher mobility in P3HT films!

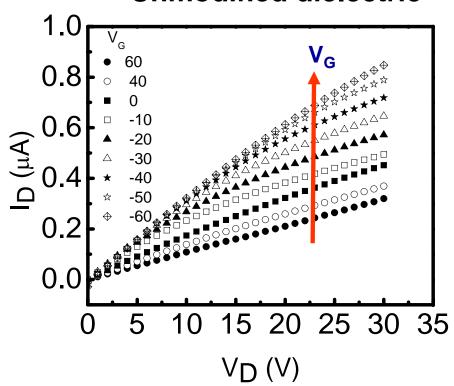
### **Schematic Diagram of OFET**

#### **Top contact Geometry**

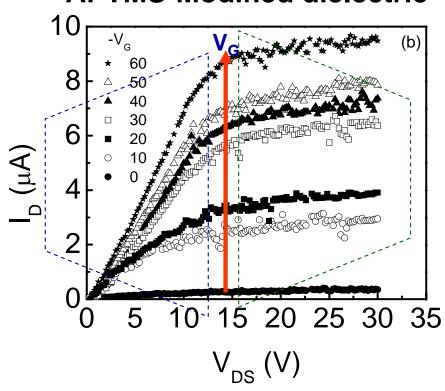


#### **OFET:** Output Characteristics

#### **Unmodified dielectric**

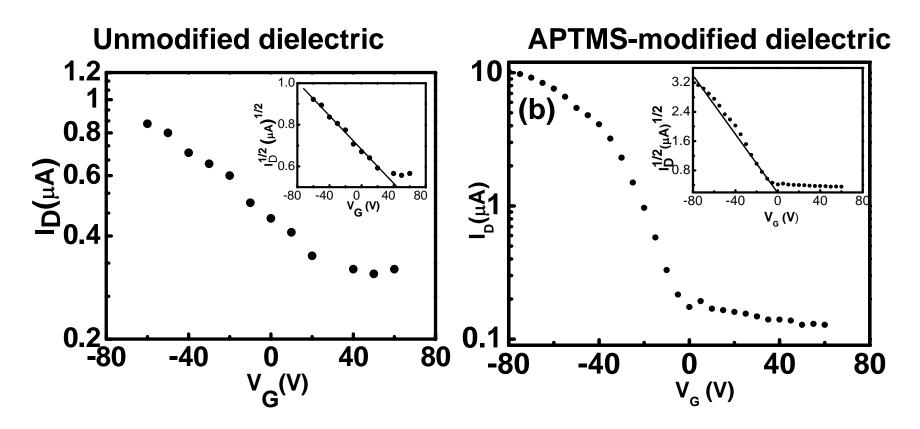


#### **APTMS-Modified dielectric**



Good ohmic contact between P3HT layer and gold.  $I_D$  for APTMS-modified OFET at  $V_G$ =0 is much lower. Clear saturation region for OFET with an modified dielectric surface

#### **OFET:** Transfer Characteristics



On/Off Ratio enhanced by two orders of magnitude

Low density of charge traps at the interface and low bulk carrier density.

#### **Calculated Parameters**

OFET using dielectric	Mobility	V <sub>t</sub> (V)	Trap density (eV <sup>-1</sup> cm <sup>-2</sup> ) x 10 <sup>15</sup>	S (V/ decade)
APTMS +SiO <sub>2</sub>	3.2x10 <sup>-2</sup>	-1.2 V	0.21	31
SiO <sub>2</sub>	0.56x10 <sup>-4</sup>	38.5	1.5	112

Low threshold voltage and trap density suggests a good interface between P3HT & APTMS.

Increased mobility for APTMS-modified FET is due to better intergranular connectivity and uniformity as well as better crystallinity and enhanced conjugation length.

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#### Conclusions



Very uniform and smooth P3HT films can be prepared on APTMS modified Si/SiO<sub>2</sub> substrates



Spectroscopic studies show high degree of molecular ordering and crystallinity in P3HT films deposited on APTMS-modified substrates



APTMS-modified gate dielectric, shows an enhanced mobility and increase in on/off ratio by two orders of magnitude

APTMS-modified substrates can significantly improve structural properties of P3HT yielding better mobility and device characteristics

### Acknowledgements

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## Thank You